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Altri autori (Persone)	LandisStefan
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Nota di contenuto	Ch. 1. X-ray lithography : fundamentals and applications -- ch. 2. NanoImprint lithography -- ch. 3. Lithography techniques using scanning probe microscopy -- ch. 4. Lithography and manipulation based on the optical properties of metal nanostructures -- ch. 5. Patterning with self-assembling block copolymers -- ch. 6. Metrology for lithography.
Sommario/riassunto	Lithography is an extremely complex tool - based on the concept of "imprinting" an original template version onto mass output - originally using relatively simple optical exposure, masking, and etching techniques, and now extended to include exposure to X-rays, high energy UV light, and electron beams - in processes developed to manufacture everyday products including those in the realms of consumer electronics, telecommunications, entertainment, and transportation, to name but a few. In the last few years, researchers

and engineers have pushed the envelope of fields including optics,
physics,
